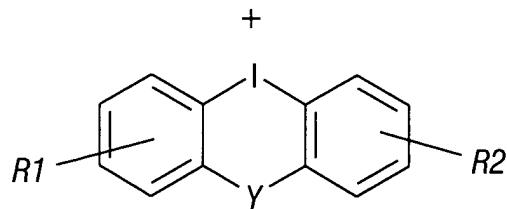
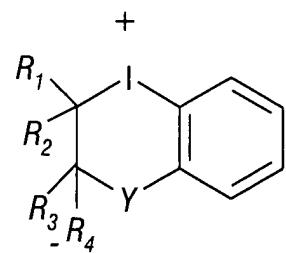


Applicant: WANG YUEH AND ERNISSE S. PUTNA  
Title: REDUCING OUTGASSING OF EXPOSURE OF PHOTOLITHOGRAPHY RESISTS  
Docket No.: ITL.1058US (P17800)  
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Sheet 1 of 1



**FIG. 1**



**FIG. 2**